

FORM PTO 1449 (modified)

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICELIST OF REFERENCES CITED BY APPLICANT(S)
(Use several sheets if necessary)

Date Submitted to PTO: August 30, 2001

ATTY DOCKET NO.
2001_1227SERIAL NO.
NEW

09/94/692

APPLICANT
Yotaro HATAMURA et al.FILING DATE
August 30, 2001

GR UP

1763

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>Asu</i>	AA	5,868,952	2/1999	Hatakeyama et al			
	AB	5,221,841	6/1993	Nagai et al			
	AC	6,010,831	1/2000	Hatakeyama et al			
	AD	5,895,582	4/1999	Wilson et al			
	AE	5,593,602	1/1997	Gelder et al			
	AF	5,411,630	5/1995	Nagase et al			
	AG	5,708,267	1/1998	Hatakeyama			
	AH	5,350,480	9/1994	Gray			
<i>Asu</i>	AI	5,883,005	3/1999	Minton et al			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
<i>Asu</i>	AJ	19,518,185 A1	11/1996	DE			
	AK						
	AL						
	AM						
	AN						

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>Asu</i>	AO	Masahiro HATAKEYAMA et al., "Fast Atom Beam (FAB) Processing with Separated Masks", The Institute of Electronics, Information and Communication Engineers, Vol. E78-C, No. 2, pp. 174-179 February 1995.
<i>Asu</i>	AP	Ichiki, K. et al, "New fast atom beam processing with separated masks for fabricating multiple microstructures" Thin Solid Films, 281-282, pp 630-633. 1996
<i>Asu</i>	AQ	Toma, Y. et al "Fast atom beam etching of glass materials with contact and non-contact masks" Jpn. J. Appl. Phys., Vol. 36, Part 1, No. 12B, pp 7655-7659. 12/1997

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*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>Auto</i>	AA	5,597,495	1/1997	Keil et al			
	AB	5,271,800	12/1993	Koontz et al			
	AC	5,817,373	10/1998	Cathey et al			
	AD	4,407,695	10/1983	Deckman et al			
	AE	5,554,303	9/1996	Kaneko et al			
	AF	5,353,182	10/1994	Nakamura et al			
	AG	4,675,075	6/1987	Sakai et al			
	AH	5,549,211	8/1996	Nakamura et al			
<i>Auto</i>	AI	5,853,959	12/1998	Brand et al			

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	AJ						
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	AN						

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>Auto</i>	AO	Toma, Y. et al "Demonstration of Fast Atom Beam Etching of Glass Materials with Contact and Non-contact masks" Dig Pap Microprocess Nanotechnol, pp148-149, 1997
	AP	
	AQ	

EXAMINER

Allen Ober

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